

WAFER HOLDER FOR SEMICONDUCTOR MANUFACTURING DEVICE AND SEMI- CONDUCTOR MANUFACTURING DEVICE IN WHICH IT IS INSTALLED

Abstract

Wafer holder for semiconductor manufacturing and semiconductor manufacturing device in which the holder is installed, the wafer holder having a wafer-carrying surface whose wafer-retaining face has an enhanced isothermal rating. In the wafer holder having a wafer-carrying surface, multiple nubs having a flat portion are formed on the wafer-carrying surface; and by making the surface area of the flats on the nubs 70 mm^2 or less per nub, distribution in obverse-surface temperature of a wafer set in place on the wafer holder can be brought within $\pm 1.0\%$. If moreover the per-nub flat surface area is 30 mm^2 or less, the temperature can be brought within $\pm 0.5\%$. In addition, the total surface area of the flats on the nubs preferably is 40% or less of the wafer surface area, inasmuch as the incidence of trouble when de-chucking the wafers can be kept under control.